CLAIMS

1. A wafer storage container apparatus for storing a stack of wafer elements, the apparatus comprising:

a wafer storage chamber for storing the stack of wafer elements, the wafer storage chamber including a base having a wafer area upon which to place the stack of wafer elements; and

a plurality of columns disposed within the wafer storage chamber, each column having a surface with a line of contact to restrict equally lateral movement of each of the wafer elements within the wafer storage chamber.

- 2. An apparatus as recited in claim 1 wherein each line of contact lies in a direction orthogonal to a plane of the wafer area.
- 3. An apparatus as recited in claim 2 wherein the wafer storage chamber includes a wall extending from the base, wherein the wall has a draft angle that facilitates removal of the wafer storage chamber from a mold.
- 4. An apparatus as recited in claim 3 wherein each column is integrally formed with the wall.
- 5. An apparatus as recited in claim 3 further comprising a cover that conforms with the wall to completely enclose the stack of wafer elements.
- 6. An apparatus as recited in claim 1 wherein the plurality of columns is in the range of three columns to six columns.
- 7. An apparatus as recited in claim 6 wherein each line of contact lies in a direction orthogonal to a plane of the wafer area.

- 8. An apparatus as recited in claim 7 wherein the wafer storage chamber includes a wall extending from the base, wherein the wall has a draft angle that facilitates removal of the wafer storage chamber from a mold.
- 9. An apparatus as recited in claim 8 wherein each column is integrally formed with the wall.
- 10. A wafer storage container apparatus for storing a stack of wafers, the apparatus comprising:
 - a wafer storage chamber;
 - at least one orientation artifact disposed within the wafer storage chamber;
 - a plurality of wafer frames adapted for insertion into the wafer storage chamber in a stack, each wafer frame including at least one alignment artifact thereon and each wafer frame being adapted to assist holding one of the wafers in a predetermined position thereon, wherein each at least one alignment artifact corresponds to a corresponding at least one orientation artifact, thereby orienting each wafer frame in the wafer storage chamber and preventing substantial rotational movement of the each wafer frame within the storage chamber; and

a plurality of columns disposed within the wafer storage chamber, each column having a surface with a line of contact to restrict equally lateral movement of each of the wafer frames within the wafer storage chamber.

- 11. An apparatus as recited in claim 10 wherein the wafer storage chamber includes: a base upon which to place the stack; and a wall connected to the base that is adapted to surround the stack.
- 12. An apparatus as recited in claim 11 wherein the orientation artifact is a wall contour artifact disposed on the wall, and wherein the alignment artifact is a contour artifact disposed on an edge of the wafer frame.

13. An apparatus as recited in claim 11 wherein:

each wafer frame includes a plurality of alignment artifacts and there exists a corresponding plurality of orientation artifacts disposed within the wafer storage container; and

each orientation artifact is a wall contour artifact disposed on a different location of the wall, and wherein each alignment artifact is a contour artifact disposed on an a different edge location of the wafer frame.

- 14. An apparatus as recited in claim 11 further comprising a cover adapted for insertion on a top of the wall.
- 15. An apparatus as recited in claim 10 wherein each wafer further includes an alignment artifact.
- 16. An apparatus as recited in claim 10 wherein each of the wafer frames includes a wafer surface on which one of the wafers rests, and the wafer surface is made of a material that assists in maintaining adhesion between the wafer frame and the wafer disposed thereon.
- 17. An apparatus as recited in claim 10 wherein each wafer frame includes a plurality of alignment artifacts and there exists a corresponding plurality of orientation artifacts disposed within the wafer storage container.
- An apparatus as recited in claim 10 wherein the plurality of columns is in the range of three columns to six columns.
- 19. An apparatus as recited in claim 18 wherein each line of contact lies in a direction orthogonal to a plane of the wafer area.
- 20. An apparatus as recited in claim 19 wherein the wafer storage chamber includes a wall extending from the base, wherein the wall has a draft angle that facilitates removal of the wafer storage chamber from a mold.

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